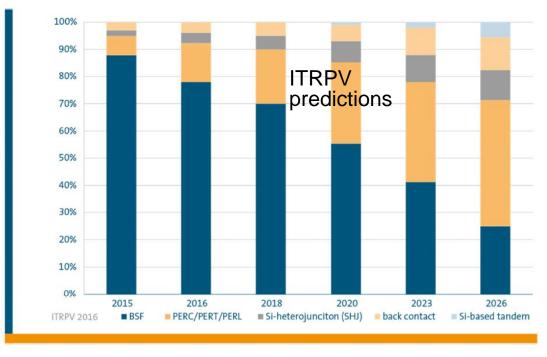


# Scientia Professor Stuart Wenham

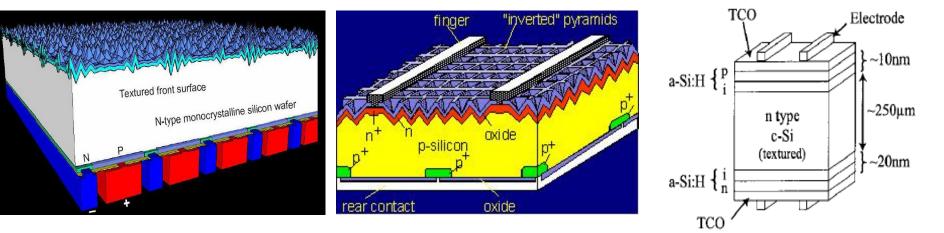
8<sup>th</sup> December, 2016

# Highest Efficiency Cell Technologies



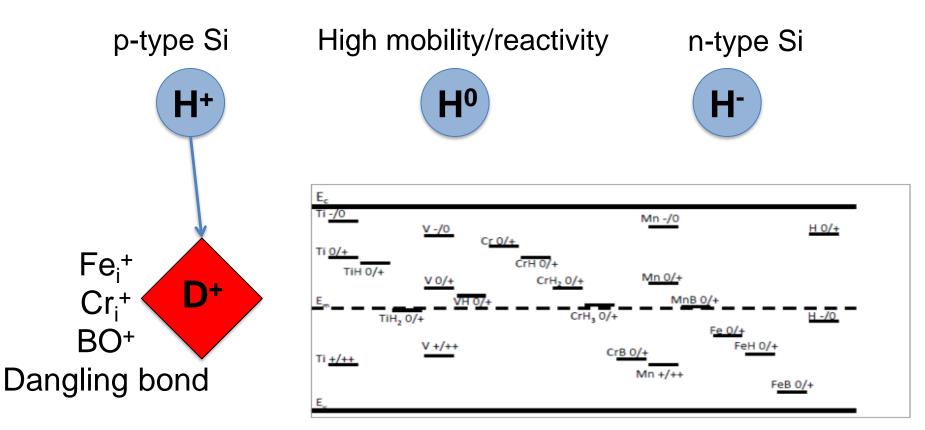
Stanford –25% rear contact

### UNSW – 25% PERC Passivated Contacts 25-26.3%





# Hydrogen very important for p-type wafers

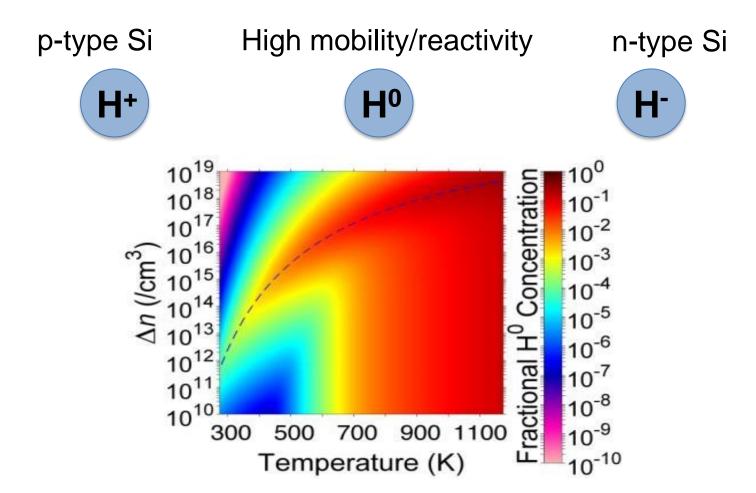


H-BO formation unfavorable in p-type silicon

Must consider the charge state of hydrogen and defects



# **Advanced Hydrogenation**

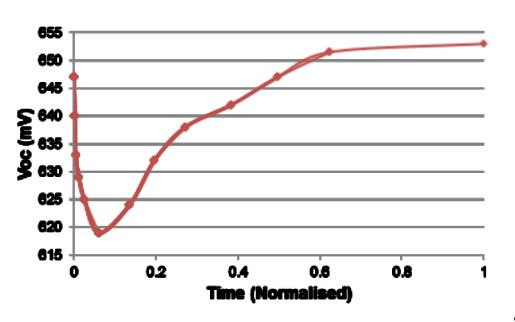


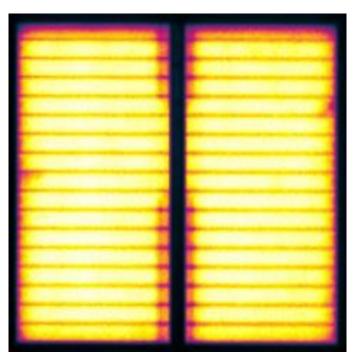
Use carrier injection and cell design to manipulate hydrogen

Now many newer and better techniques for controlling the H charge state

# Application to p-type Cz wafers

- Main issue solving LID (B-O defects)
- Accelerated defect formation
- UNSW Advanced Hydrogenation of B-O defects
- LID in p-type Cz PERC cell Solved!!

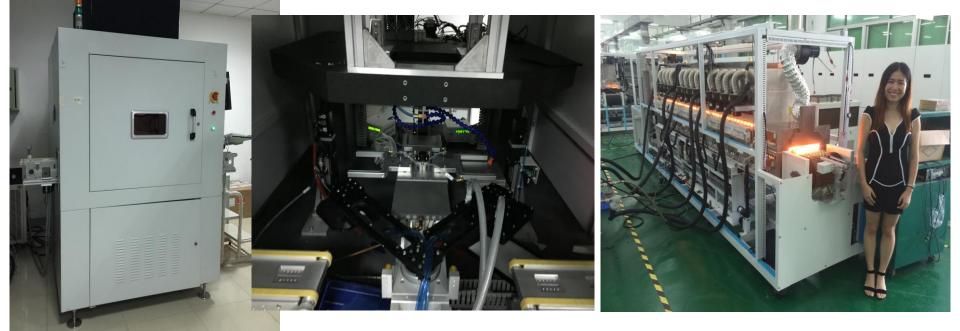




**Sequential Photoluminescence Images** 



### Advanced Hydrogenation Commercialisation

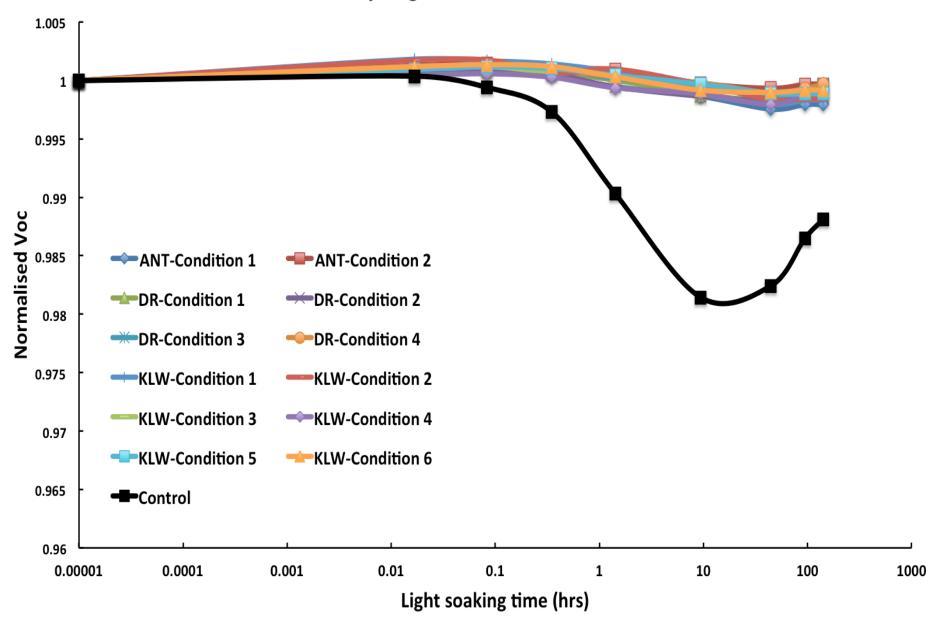




- Provide control of the hydrogen charge state
- New tools implementing UNSW hydrogenation
  - Asia Neo Tech (Taiwan LED based tool)
  - Ke Long Wei (China Broad spectrum tool)
  - Schmid (Germany)
  - Dr Laser (China Laser-based tool)
  - Meyer Berger (Switzerland)
- New generation of tools in 2017 with solution for multi LID

### **Evaluation of commercial prototypes**

Cz PERC hydrogenation tools evaluation



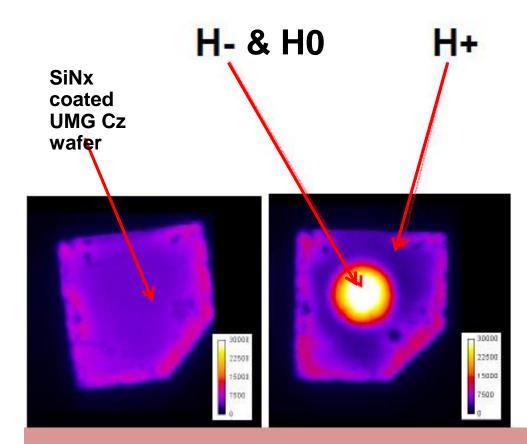
## Advanced Hydrogenation of P-type Cz PERC

PERC cell producers	Hydrogenatio n Efficiency Increases (% absolute)	48 h light soak stable?	21.0 Efficiency Hydrogenated group Non-hydrogenated group
Manufacturer A	+0.8%	Yes	
Manufacturer B	+1.0%	Yes	(%) 20.0 - Constraints - 19.5 -
Manufacturer C	+0.7%	Yes	<sup>™</sup> U U U U 19.5 –
Manufacturer D	+0.9%	Yes	
Manufacturer E	+1.5%	Yes	18.5
Manufacturer F	+0.8%	Yes	Before hydrogenation After hydrogenation 48hr light soak
Manufacturer G	+1.8%	Yes	<ul> <li>→ Final efficiency higher</li> <li>→ Final efficiency stable</li> </ul>
Average Increase	+1.1% absolute	Yes	$\rightarrow \text{ PERC cells need this}$

### H can passivate much more than B-O defects

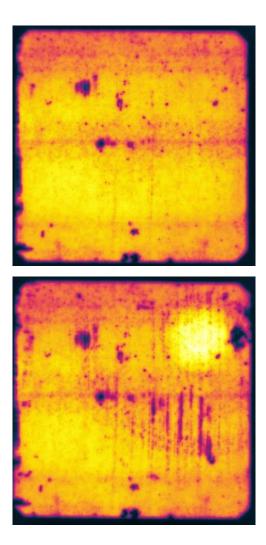
#### Localised Control of the H Charge State

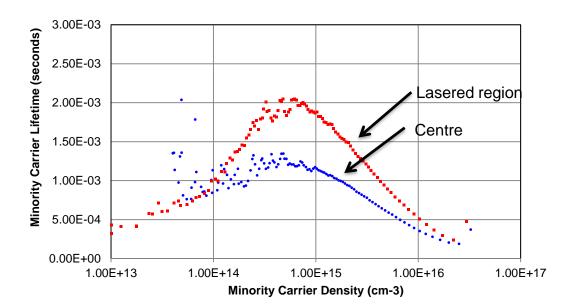
- Innovative hydrogen charge state control has large impact on both diffusivity & reactivity of hydrogen atoms in silicon
- Transformation of low quality silicon into high quality silicon (where PL count saturates)
- Simple 8 second process
- US Patent awarded Nov 2015
   without modification



# PL Images before & after localised hydrogenation. Wafer T = 250 degC

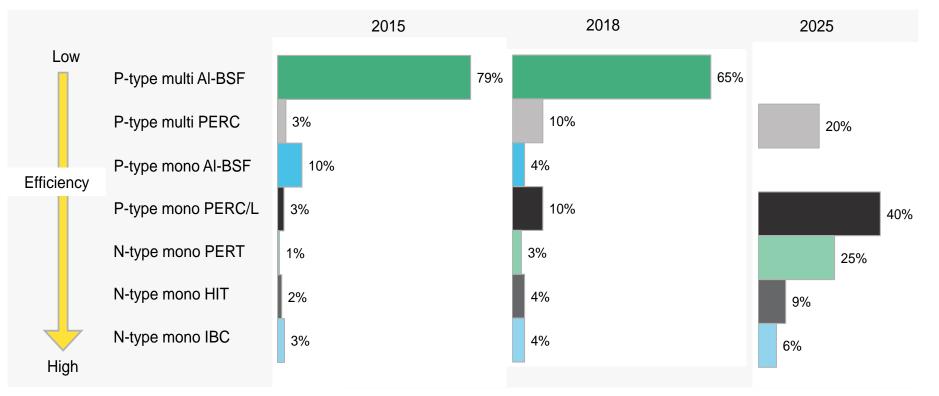
### Advanced Hydrogenation also works well on n-type!







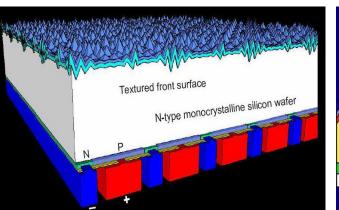
# Cell Technology Trends – Bloomberg New Energy

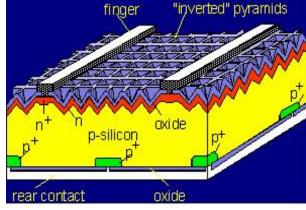


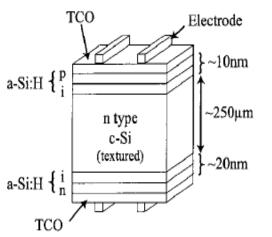
Stanford –25% rear contact

UNSW – 25% PERC

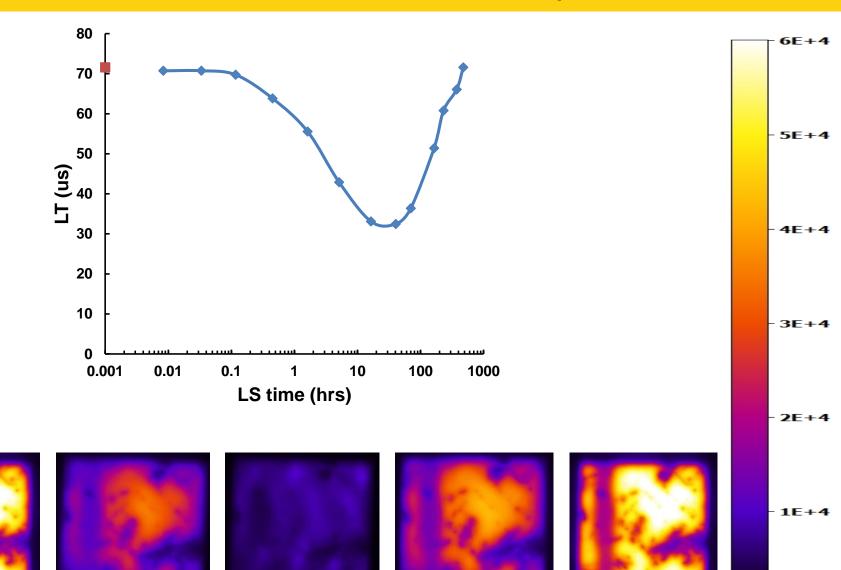
#### Passivated Contacts 25-26.3%







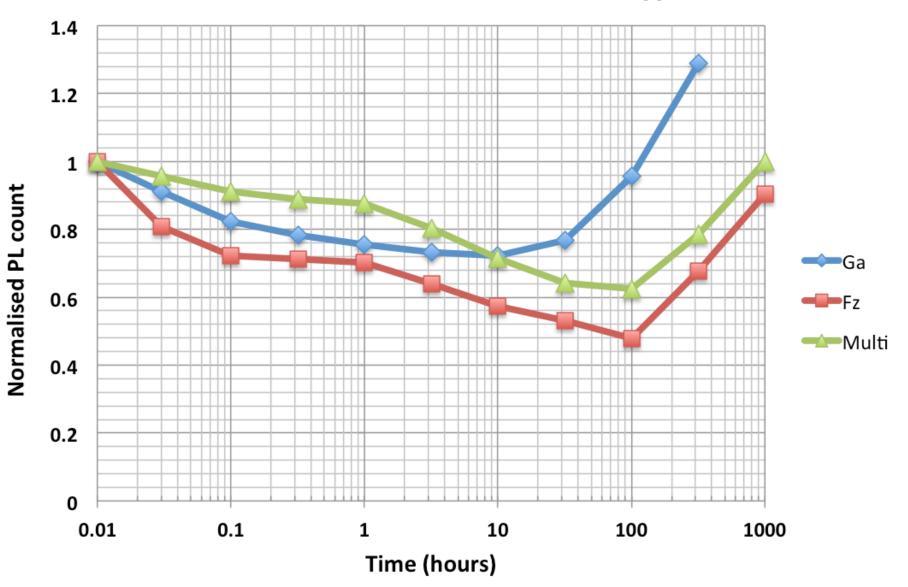
### LID in multi-PERC is a serious problem



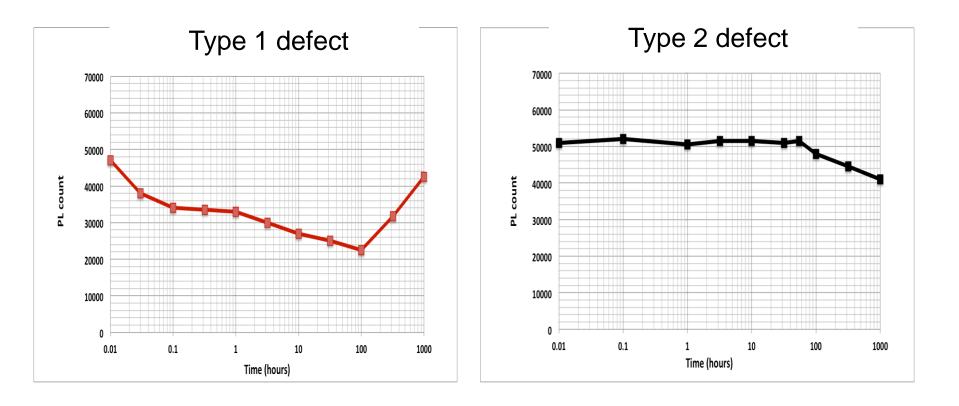
Aft Firing16.4hrs40.4hrs232hrs800hrsPL response as function of light-soaking time

### Defect causing LID in mc-Si PERC also occurs in mono-Si

#### Normalised LID for different wafer types

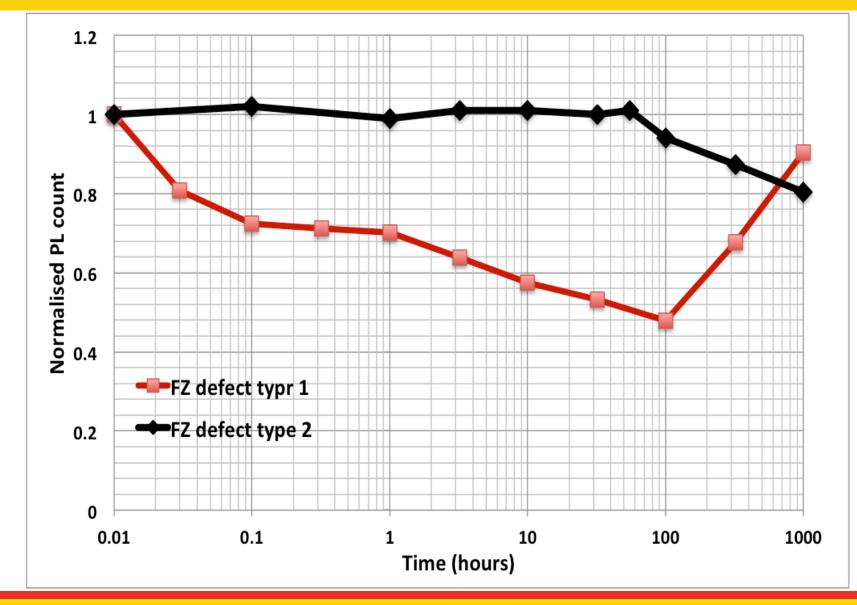


### Comparison of Type 1 & 2 Defects

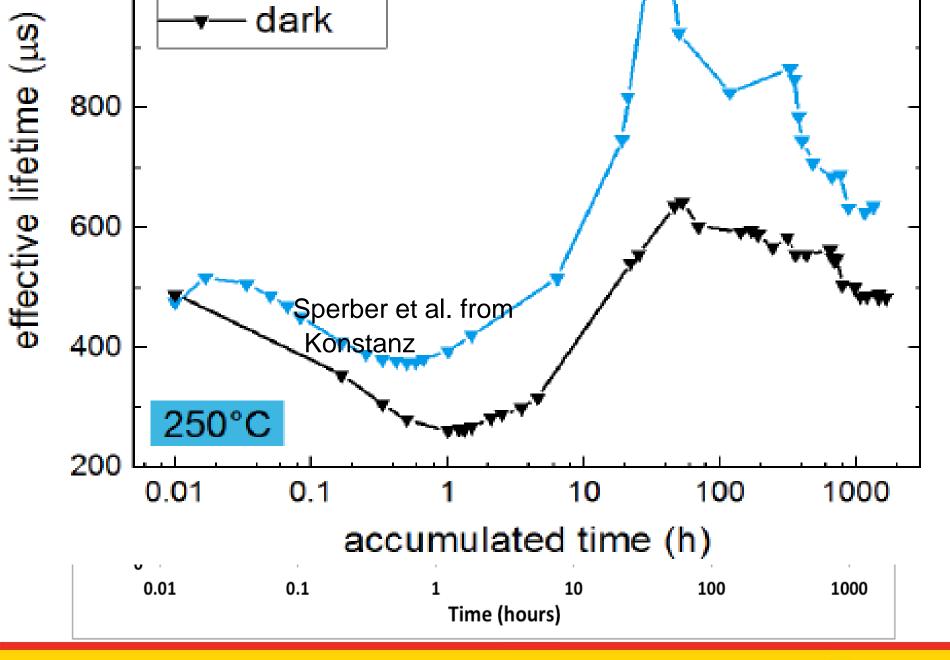




### Identification of same defect in FZ wafers



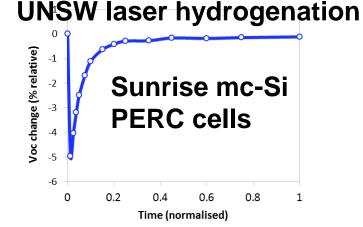


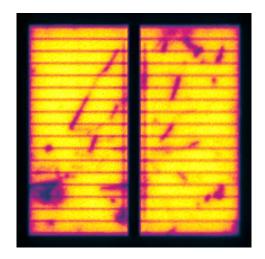




### Elimination of LID in mc-Si PERC cells

- Identification of the defect in mc-Si
- Multiple energy levels in band-gap
- H accelerates evolution of defect
- H ultimately passivates defect
- Need >1,000 hours of light-soaking
- Common in n-type material
- Can occur in any wafers including mono wafers





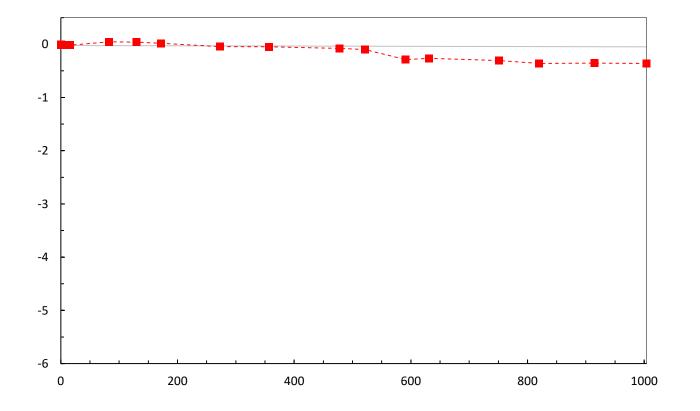
Top: Relative change in V<sub>oc</sub> of a mc-Si PERC cell with continual laser treatment
 Bottom: Associated photoluminescence images



#### Best published stability – Re-fire and laser Type 2 defect appears to be mitigated $\Delta V_{\infty}$ from initial value before re-firing (% relative) -2 No treatment -3 Fire only Laser ony Fire, laser -4 -5 Treatment 50 0 100 150 200 250 300 350 400 450 Light soak time at 70 °C, 0.46 kW/m<sup>2</sup> (h)



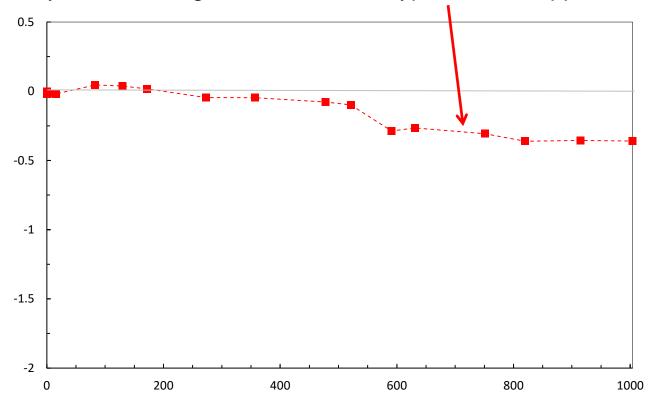
# Best published stability – Re-fire and laser





# Best published stability – Re-fire and laser

Zoom in on y-axis shows gradual decline as type 2 defect appears:

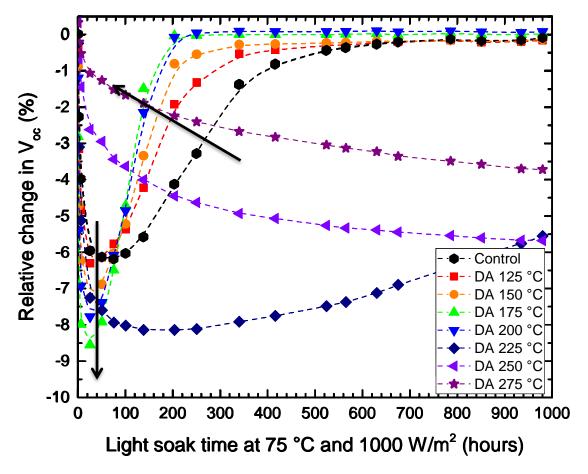




# Dark annealing as an accelerated ageing test

Dark annealing can accelerate the evolution of the degradation

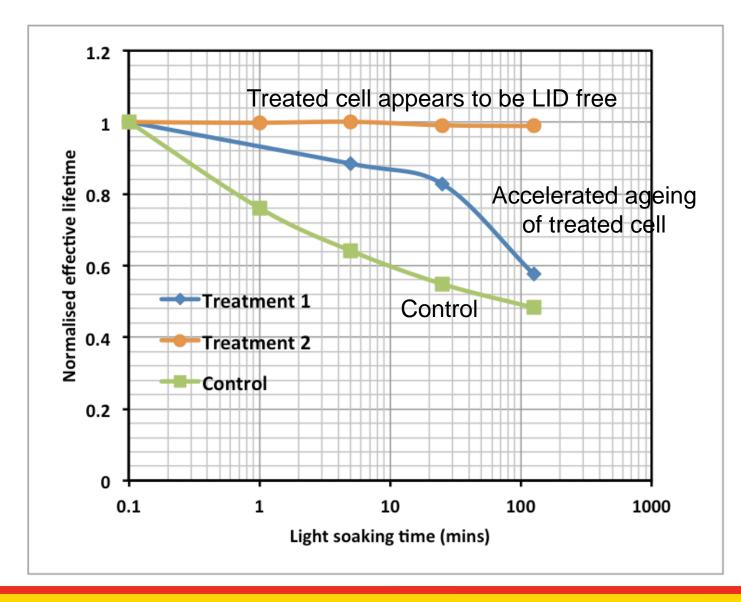
- 8 identical sister mc-Si PERC cells
- Each dark annealed at a different temperature for 2.5 hours, then light soaked at standard 75 C 1kW/m2
- Dark annealing first accelerates type 1 defect forming and recovering
- Eventually, the dark annealing eliminates the type 1 defect, and only the type 2 defect remains
- → Dark annealing can be used as an accelerated test for future Type
   2 degradation



[UNSW unpublished]



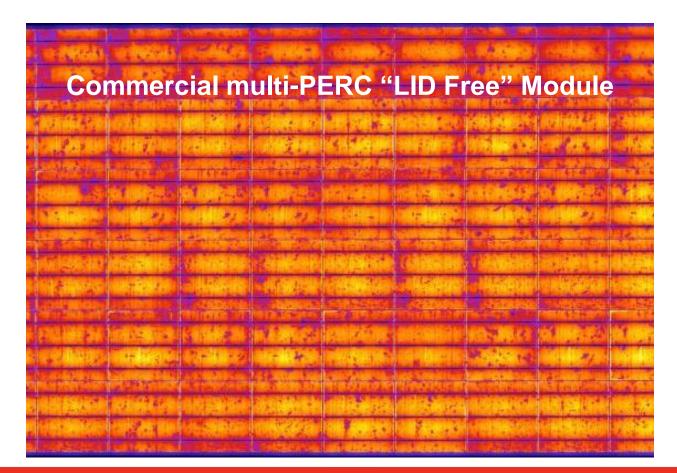
# Standard light-soaking is not suitable





# Accelerated testing on "LID free" modules

• Accelerated by 150 °C dark anneal for 10 hours prior to light soaking

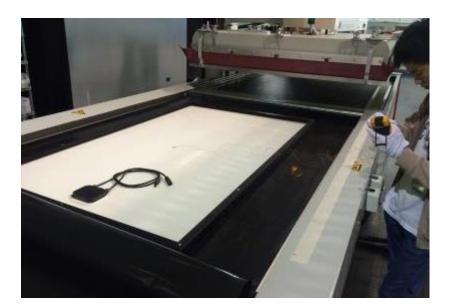




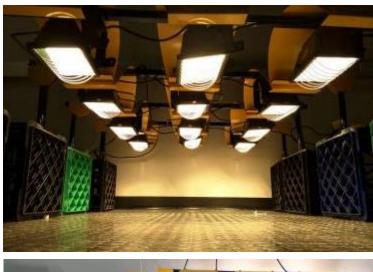
# Dark anneal

# &

# Light Soak









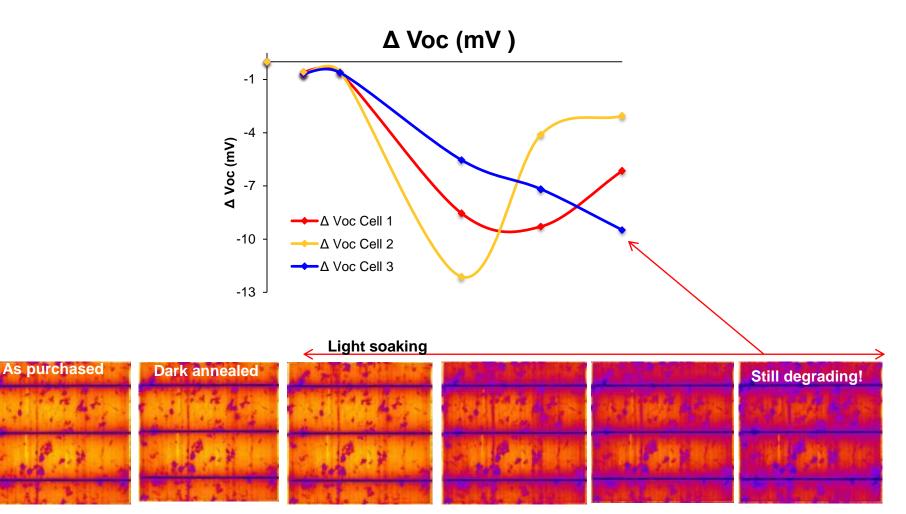


# Accelerated testing on "LID free" modules





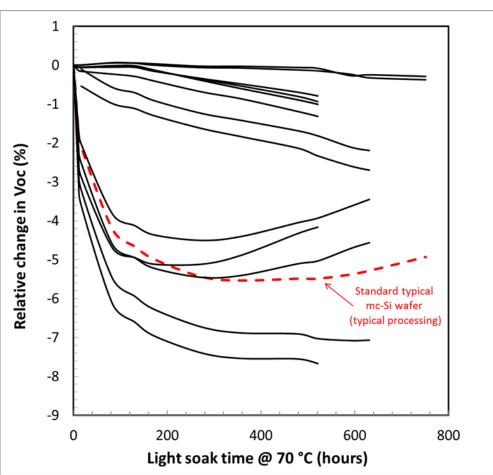
# Cell 3





### Identification of the defect causing LID in mc-Si PERC

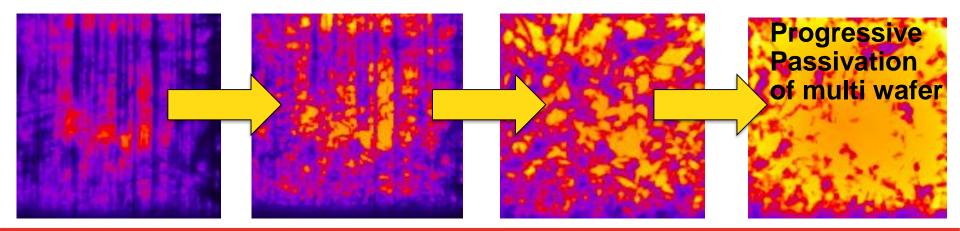
- Defect takes on 2 forms:
   type 1 and type 2
- 2 energy levels in band-gap make its behaviour confusing
- Unique approach to H charge state control fixes defects
- Can be added to any wafer
- Present in Cz
- Common in n-type material
- Damages bulk lifetimes
- Damages AIOx passivation





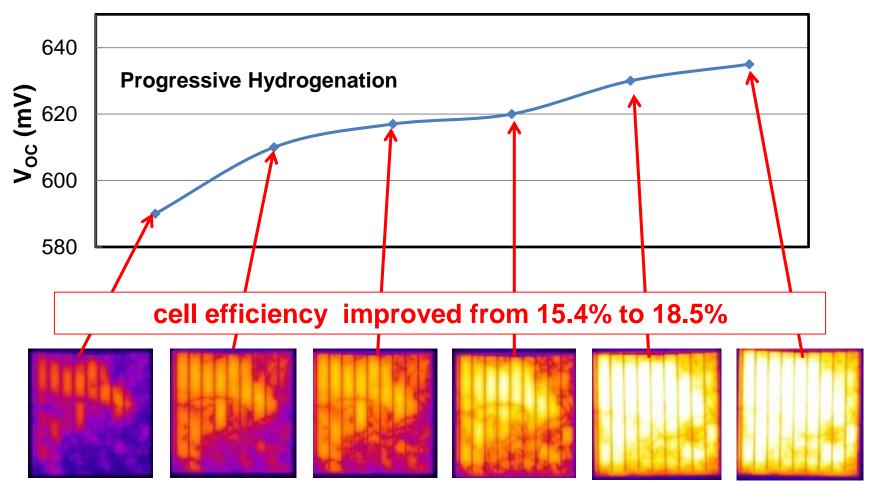
### Greatest opportunity is with multicrystalline silicon

- Large range of types of defects
  - Crystallographic defects e.g. grain boundaries, dislocations etc
  - Contaminants
  - Variability across wafers and between wafers
- LID has major impact
- PERC cells >20% efficiency if not for LID
- Large range of defects makes H passivation more complicated but also increases its importance





### Progressive improvement through repeated Hydrogenation



Progressive photoluminescence images (open circuit) for cells progressively hydrogenated



# Advanced hydrogenation solves Rs and LID in multi

- Solutions will be published in 2017
- Consortium of 20 companies funding & commercialising the technology
- Industry partners like more patents
- Strong patent portfolio

#### Advanced hydrogenation of silicon solar cells US 9190556 B2

CLAIMS (21)

The invention claimed is:

1. A method of processing silicon, with a hydrogen source present, for use in the fabrication of a photovoltaic device having at least one rectifying junction, the method comprising heating at least a region of the device to at least 100° C. while simultaneously illuminating at least some of the device with at least one light source whereby the cumulative power of all the incident photons with sufficient energy to generate electron hole pairs within the silicon is at least 20 mW/cm<sup>2</sup>.



### 6 new patents for manipulating H and the H charge state

- Autogeneration of H0 for enhanced hydrogen passivation
- Controlling the location of hydrogen within silicon
- Enhanced generation of H0 in n-type silicon
- Novel thermal manipulation of hydrogen
- Use of hydrogen sinks to control hydrogen flow
- Solving LID in multicrystalline silicon wafers



# Summary

- Hydrogen passivation is greatly enhanced through control of the H charge state to improve diffusivity and reactivity
- Large consortium of industry partners supporting the work
- Key patents awarded
- Commercial tools now available
- It appears most defect types can be passivated
- B-O related LID rapidly mitigated 8 sec for full recovery
- Defect X causing LID in mc-Si has been identified
- Defect X also relevant to mono and needs different hydrogen passivation process



# Thank you





